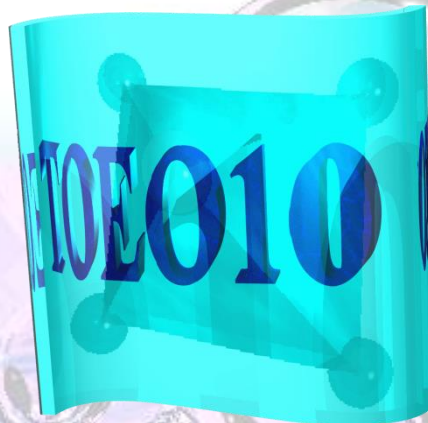


10th International Symposium on Transparent Oxide and Related Materials for Electronics and Optics

ABSTRACT Book



July 3-5, 2017

International Conference Center, Waseda University, Tokyo, Japan

Sponsor

The 166th Committee on Photonic & Electronic Oxide,
Japan Society for the Promotion of Science (JSPS)

Supported by

The Japan Society of Applied Physics
The Japanese Association for Crystal Growth
The Materials Research Society of Japan
New Glass Forum
The Physical Society of Japan
The Vacuum Society of Japan

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Organization

■ Sponsor

- ◇ The 166th Committee on Photonic & Electronic Oxide, Japan Society for the Promotion of Science (JSPS)

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- ◇ The Japan Society of Applied Physics
- ◇ The Japanese Association for Crystal Growth
- ◇ The Materials Research Society of Japan
- ◇ New Glass Forum
- ◇ The Physical Society of Japan
- ◇ The Vacuum Society of Japan

■ Organizing Committee:

Chairs

- ◇ Toshio Kamiya (Tokyo Tech., Japan)
- ◇ Hideo Hosono (Tokyo Tech., Japan)
- ◇ David S. Ginley (NREL, USA)
- ◇ C.G. Granqvist (Uppsala Univ., Sweden)
- ◇ G. Kiriakidis (Univ. Crete / IESL-FORTH, Greece)

International Advisory Committee

- ◇ N. Ichinose (Waseda Univ., Japan)
- ◇ K. Ellmer (Helmholtz-Zentrum für Materialien und Energie Berlin, Germany)
- ◇ G. Kiriakidis (Univ. Crete / IESL-FORTH, Greece)
- ◇ Y. Shigesato (Aoyama Gakuin Univ., Japan)
- ◇ P.-K. Song (Pusan Natnl. Univ., Korea)

Organizing Committee Members

- ◇ T. Asahi (Waseda Univ., Japan)
- ◇ N. Fujimura (Osaka Prefecture Univ., Japan)
- ◇ Y. Hari (Canon-Anelva, Japan)
- ◇ T. Kitamura (Fujikura Ltd., Japan)
- ◇ T. Kubo (JX Nippon Oil & Energy, Japan)
- ◇ T. Minami (Kanazawa Inst. Tech., Japan)
- ◇ T. Miyata (Kanazawa Inst. Technol., Japan)
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- ◇ N. Ohashi (NIMS, Japan)

- ◇ N. Oka (Kindai Univ., Japan)
- ◇ H. Odaka (Asahi Glass Corporation, Japan)
- ◇ Y. Sato (Okayama Univ. of Sci., Japan)
- ◇ H. Segawa (NIMS, Japan)
- ◇ Y. Shigesato (Aoyama Gakuin Univ., Japan)
- ◇ K. Shimamura (NIMS, Japan)
- ◇ T. Uchida (Tokyo Polytech. Univ., Japan)
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- ◇ K. Utsumi (Tosoh Corporation, Japan)
- ◇ N. Yamada (Chubu Univ., Japan)
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Program Committee

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- ◇ H. Hosono (Tokyo Tech., Japan)
- ◇ Y. Shigesato (Aoyama Gakuin Univ., Japan)
- ◇ T. Kamiya (Tokyo Tech., Japan)
- ◇ T. Odaka (Asahi Glass Corporation, Japan)
- ◇ K. Shimamura (NIMS, Japan)

General information

■ Period

Monday, July 3 – Wednesday, July 5, 2017

■ Venue

International Conference Center, Waseda University
1-20-14, Nishi-Waseda, Shinjuku-ku, Tokyo 169-0051, Japan

■ Topics

I. Materials

- ITO alternatives
- Transparent conducting oxides (TCO)
- Transparent oxide semiconductors (TOS)
- Low dimensional materials, graphene, nanocarbon, other related conductors
- Multi / Coupled functional materials
- Photovoltaic materials
- Light emitting materials
- Photocatalysts
- Flexible materials
- Optic / Electronic functional oxides: Synthesis, Characterization, and Application
- Materials design, Development of new materials

II. Processes

- Low-temperature, Non-vacuum, Green process
- Sputtering (pulsing, web coater, etc)
- PLD, CVD, PVD, Atmospheric plasma, ALD
- Sol-gel, Ink-jet, Printing
- New deposition method

III. Devices and Applications

- Photovoltaic devices
- Transparent optoelectronic devices
- Optoelectronic devices using TCOs and TOSs
- Thin-film transistor (TFT)
- Touch / Gas / Bio sensors
- Flat-panel display (FPD) / OLED / Electronic paper / Flexible devices, etc
- Other devices: FET, UV-LED, FED, Sensor, etc

■ Invited Speakers

- Y. Chen (Tohoku Univ., Japan)
- Z. Cui (Chinese Academy of Sciences, China)
- K. Ellmer (Helmholtz Center, Germany)
- D. S. Ginley (NREL, USA)
- C. G. Granqvist (Uppsala Univ., Sweden)
- L. Han (NIMS, Japan)
- T. Hasegawa (Univ. Tokyo, Japan)
- G. Hautier (Univ. Catholique de Louvain, Belgium)
- H. Hosono (Tokyo Tech., Japan)
- T. Kamiya (Tokyo Tech., Japan)
- G. Kiriakidis (Univ. Crete/FORTH, Greece)
- T. Marks (Northwestern Univ., USA)
- J. McKittrick (Univ. California, USA)
- M. K. Nazeeruddin (Ecole Polytech. Lausanne, Switzerland)
- K. Park (LG Display, Korea)
- H. Segawa (Univ. Tokyo, Japan)
- Y. Shigesato (Aoyama Gakuin Univ., Japan)
- B. Szyszka (Berlin Institute of Technology, Germany)
- T. Uchida (Tokyo Polytechnic Univ., Japan)
- N. Yamada (Chubu Univ., Japan)
- H. Ye (Zhejiang Univ., China)
- K. Yoshimura (AIST, Japan)

■ Official language

English

■ Home page

<http://conf.msl.titech.ac.jp/Conference5/TOEO10/wiki/>

■ E-mail

tkamiya@msl.titech.ac.jp

■ Information for Presentation

1. Oral presentation @ 1st floor (ground floor)

- Oral presentations are 25 minutes + 5 minutes (presentation + discussion) for invited talks, and 12 minutes + 3 minutes for contributed orals.
- The presentation room is equipped with a computer projector.
- Presentators are advised to bring own notebook PCs.
- A notebook PC is equipped in the presentation room. Instruction is provided at the symposium when and how their presentation files should be transferred to the notebook PC prior to the presentation.

2. Poster presentation (Oral short presentation @ 1st floor, Poster @ 3rd floor)

- The presenting author of a poster paper is requested to give a **one-minute oral short presentation**, which is scheduled to be before the corresponding poster presentations and held at **1st floor**.
- All the posters are requested to be displayed from Monday noon in order that participants can see them during lunch time and coffee breaks.
- Poster presentation sessions will be held on
 - ◇ **Monday, July 3 from 16:45 to 19:00 at 3rd floor.**
- The size of a poster board is 114 cm wide and 168 cm high, suitable for a poster size up to the A0 format (84 cm wide and 119 cm high).
- Each presentation will have a board labeled with the program number.
- Sticky tapes or pushpins may be used to fix the posters. These are available at the poster room but would be of limited number.

■ Wifi

Participants may use eduroam and are advised to get an eduroam account prior to the symposium.

■ Official travel agency

Keio Travel Agency (KTA)

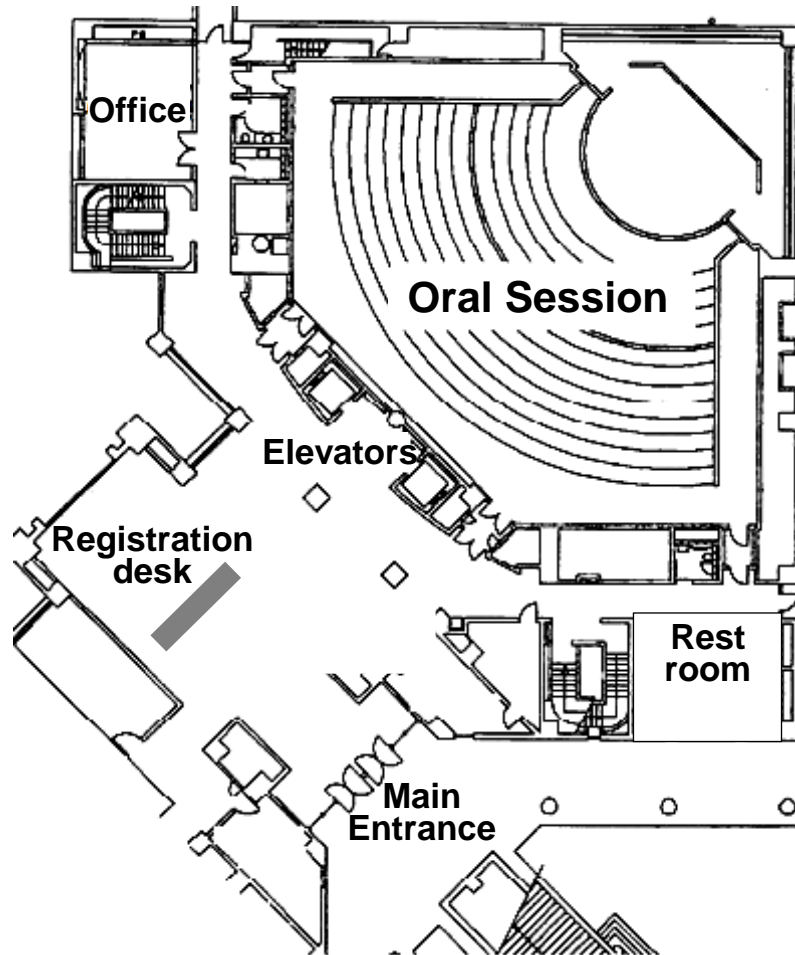
URL: <http://www.kingtour.com/> (only in Japanese)

■ Waseda Town Guide

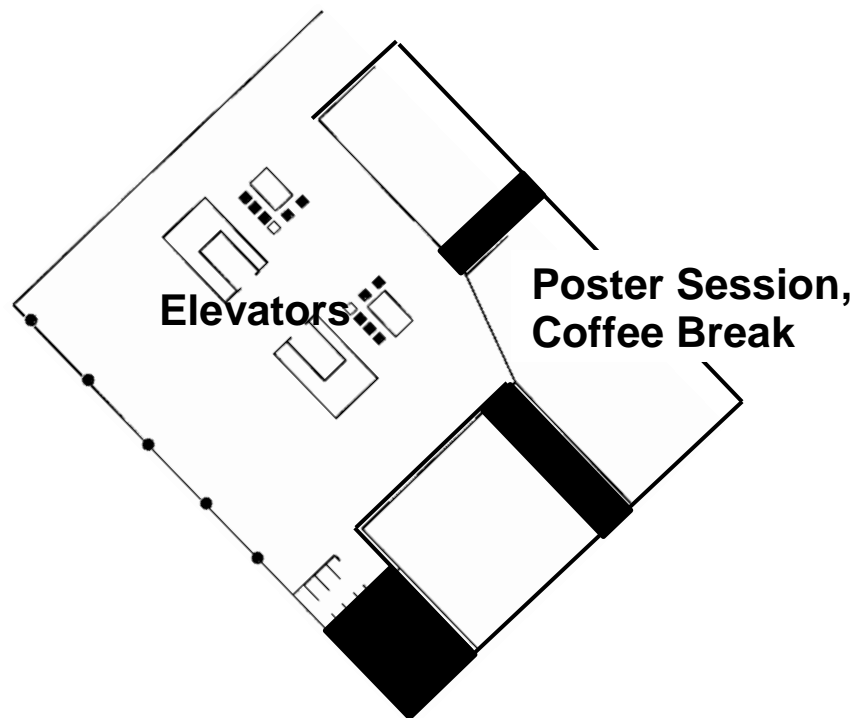
URL: <http://www.waseda.jp/rps/irp/HP.pdf>

■ **Floor Plan**

[1st Floor (ground floor), International Conference Center, Waseda University]



[3rd Floor, International Conference Center, Waseda University]



Schedule & Timetable

■ Monday, July 3, 2017

Time	Paper #	Session (Chair)	Presenter
09:00-09:15	Registration		
09:15-09:30			
09:30-09:45			
09:45-10:00			
10:00-10:15			
10:15-10:30	Opening address		T. Kamiya (Tokyo Tech, Japan)
10:30-10:45	3aI01	Computational Material Design (Chair: T. Marks)	D. S. Ginley (NREL, USA)
10:45-11:00			
11:00-11:15	3aI02		Y. Chen (Tohoku Univ., Japan)
11:15-11:30			
11:30-11:45	3aI03		G. Hautier (Univ. Catholique de Louvain, Belgium)
11:45-12:00			
12:00-12:15	Lunch		
12:15-12:30			
12:30-12:45			
12:45-13:00			
13:00-13:15			
13:15-13:30			
13:30-13:45			
13:45-14:00	3pI04	TCO applications (Chair: G. Hautier)	H. Ye (Zhejiang Univ., China)
14:00-14:15			
14:15-14:30	3pI05		T. Marks (Northwestern Univ., USA)
14:30-14:45			
14:45-15:00	3pP11- 3pP23	Short presentation 02 (Chair: N. Oka)	(1 min. Talk)
15:00-15:15	Coffee break		
15:15-15:30			
15:30-15:45	3pP24- 3pP34	Short presentation 03 (Chair: J. Junjun)	(1 min. Talk)
15:45-16:00	3pI06	Functional Oxides (TOS and TCO) (Chair: D. S. Ginley)	Y. Shigesato (Aoyama Gakuin Univ., Japan)
16:00-16:15			
16:15-16:30	3pO01		K. Ide (Tokyo Tech., Japan)
16:30-16:45	3pO02		M. Ota (Tokyo Tech., Japan)
16:45-17:00	3pP01- 3pP34	Poster session	
17:00-17:15			
17:15-17:30			
17:30-17:45			
17:45-18:00			
18:00-18:15			
18:15-18:30			
18:30-18:45			
18:45-19:00			

■ Tuesday, July 4, 2017

Time	Paper #	Session (Chair)	Presenter
09:00-09:15	Registration		
09:15-09:30			
09:30-09:45			
09:45-10:00			
10:00-10:15			
10:15-10:30	4aI01	New Materials (Chair: Z. Cui)	N. Yamada (Chubu Univ., Japan)
10:30-10:45			
10:45-11:00	4aO01		K. Miura (Osaka Prefecture Univ., Japan)
11:00-11:15	4aI02		J. McKittrick (Univ. California, USA)
11:15-11:30			
11:30-11:45	4aO02		T. Mizunami (Kyutech, Japan)
11:45-12:00	Lunch		
12:00-12:15			
12:15-12:30			
12:30-12:45			
12:45-13:00			
13:00-13:15			
13:15-13:30			
13:30-13:45			
13:45-14:00	4pI04	H. Segawa (Univ. Tokyo, Japan)	
14:00-14:15			
14:15-14:30	4pI05	L. Han (NIMS, Japan)	
14:30-14:45			
14:45-15:00	4pO03	S. Nakagomi (ISU, Japan)	
15:00-15:15	4pO04	T. Toyoda (UEC, Japan)	
15:15-15:30	Coffee break		
15:30-15:45			
15:45-16:00	4pI06	Transparent Oxide Semiconductors, Photocatalysts (Chair: J. McKittrick)	Z. Cui (Chinese Academy of Sciences, China)
16:00-16:15			
16:15-16:30	4pO05		H. Yang (Tokyo Tech., Japan)
16:30-16:45	4pO06		N. Watanabe (Tokyo Tech., Japan)
16:45-17:00			
17:00-17:15	4pI07		G. Kiriakidis (Univ. Crete/FORTH, Greece)

■ Wednesday, July 5, 2017

Time	Paper #	Session (Chair)	Presenter
09:00-09:15	Registration		
09:15-09:30			
09:30-09:45	5aI01	Display Materials, Devices (Chair: C. G. Granqvist)	T. Kamiya (Tokyo Tech., Japan)
09:45-10:00			
10:00-10:15	5aI02		T. Uchida (Tokyo Polytechnic Univ., Japan)
10:15-10:30			
10:30-10:45	5aI03		H. Hosono (Tokyo Tech., Japan)
10:45-11:00			
11:00-11:15	5aI04		K. Park (LG Display, Korea)
11:15-11:30			
11:30-11:45	Lunch		
11:45-12:00			
12:00-12:15			
12:15-12:30			
12:30-12:45	5pI05	New fabrication methods (Chair: T. Uchida)	T. Hasegawa (Univ. Tokyo, Japan)
12:45-13:00			
13:00-13:15	5pO01		X. Fu (NIMS, Japan)
13:15-13:30	5pI06		B. Szyszka (TU Berlin, Germany)
13:30-13:45			
13:45-14:00	5pI07		K. Ellmer (Helmholtz-Zentrum Berlin, Germany)
14:00-14:15			
14:15-14:30	Coffee break		
14:30-14:45			
14:45-15:00	5pI08	Optical applications (Chair: K. Ellmer)	K. Yoshimura (AIST, Japan)
15:00-15:15			
15:15-15:30	5pI09		C. G. Granqvist (Uppsala Univ., Sweden)
15:30-15:45			
15:45-16:00	Closing (Later paper)		Y. Shigesato (Aoyama Gakuin Univ., Japan)

PROGRAM

Date: July 3, 2017

Oral Session: Computational Material Design

10:30-11:00

3aI01 Computational Design and Realization of Functional Metastable Materials (INVITED)
D. Ginley^{*)}, G. Ceder²⁾, K. Persson²⁾, M. Toney³⁾, S. Lany¹⁾, J. Tate⁴⁾ and W. Tumas¹⁾
¹⁾National Renewable Energy Laboratory, Golden, CO 80401 ²⁾ Lawrence Berkeley National Laboratory, Berkeley CA ³⁾ SLAC National Accelerator Laboratory, Palo Alto CA ⁴⁾Oregon State University, Corvallis, OR 97331

11:00-11:30

3aI02 First-Principles Modeling of Several Functional Oxides (INVITED)
Y. Chen^{1,*)}, A. Saengdeejing¹⁾, T. Mohri²⁾ and S. Iwata³⁾
¹⁾ School of Engineering, Tohoku University, Sendai, JAPAN ²⁾ Institute for Materials Research, Tohoku University, Sendai, JAPAN ³⁾ The Graduate School of Project Design, Tokyo, JAPAN

11:30-12:00

3aI03 High-Throughput Computational Search for New High Mobility Transparent (Semi)Conducting Oxides (INVITED)
G. Hautier
Institute of Condensed Matter and Nanosciences, Université catholique de Louvain, Belgium

Short Presentation 01

13:30-13:45

- 3pP01 Second-Harmonic Generation in Thermally Poled Twin-Hole Silica-Glass Fiber by Quasi-Phase Matching with Excimer-Laser Exposure: Optimization by Fiber Stretch**
T. Mizunami, *Y. Itoh and R. Sasaki
Department of Electrical Engineering and Electronics, Graduate School of Engineering, Kyushu Institute of Technology,
- 3pP02 Vanadate Glass As Oxygen Electrodes for Metal-Air Rechargeable Battery**
H. Miyamoto^{1,*)}, M. Yuasa¹⁾, T. Nishida¹⁾ and N. Oka¹⁾
¹⁾ Department of Biological and Environmental Chemistry, Kindai University, Japan
- 3pP03 Real-Time Sweat PH Sensing of Flexible ISFET for Healthcare Application**
S. Nakata^{1,*)}, T. Arie¹⁾, S. Akita¹⁾ and K. Takei¹⁾
¹⁾ Department of Physics and Electronics, Osaka Prefecture University, Japan
- 3pP04 Indium Zinc Tin Oxide Thin Film Transistors with TiO₂ Gate Dielectric**
M. Putri^{1,*)}, Y.W. Heo²⁾ and H.Y. Lee¹⁾
¹⁾ School of Materials Science and Engineering, Yeungnam University, Gyeongsan, 38541 REPUBLIC OF KOREA ²⁾ School of Materials Science and Engineering, Kyungpook National University, Daegu, 41566 REPUBLIC OF KOREA
- 3pP05 Omnidirectional Reflector with TIR Interface for Light Extracion Enhancement of Solid-State Light Source**
K. Yamae^{1,2,*)}, H. Fukshima¹⁾ and K. Fujimoto²⁾
¹⁾ Panasonic Corporation, Eco Solutions Company ²⁾ Graduate School of Engineering, Osaka University
- 3pP06 Ln³⁺ 4f Energy Levels in CaTiO₃ Analyzed by XPS Measurements**
R. Yamamoto^{*)} and K. Ueda
Department of Materials Science, Graduate School of Engineering, Kyushu Institute of Technology, 1-1 Sensui, Tobata, Kitakyushu 804-8550, JAPAN

- 3pP07 Inverted Organic Light-Emitting Diodes Using Polyethylenimine with Different Chemical Structures As An Electron Injection Layer**
T. Mayumi^{1,*}, M. Takada¹, K. Morii², T. Nagase^{1,3}, T. Kobayashi^{1,3} and H. Naito^{1,3}
¹ Department of Physics and Electronics, Osaka Prefecture University, JAPAN ² Nippon Shokubai Co., Ltd., JAPAN ³ The Research Institute for Molecular Electronic Devices (RIMED), Osaka Prefecture University, JAPAN
- 3pP08 Mössbauer Spectra of Highly Conductive Vanadate Glass Containing Tin Oxide**
Y. Fujita^{1,*}, T. Izumi¹, S. Kubuki², T. Nishida¹ and N. Oka¹
¹ Kindai University, Japan ² Tokyo Metropolitan University, Japan
- 3pP09 Identification of Transparent Plastic in Milliseconds Using Raman Spectroscopy**
W. Musu^{1,*}, A. Tsuchida², H. Kawazumi¹ and N. Oka¹
¹ Department of Biological and Environmental Chemistry, Kindai University, JAPAN ² Saimu Corporation, JAPAN
- 3pP10 Photovoltaic Properties of Cu₂O-Based Heterojunction Solar Cells Using N-Type Oxide Semiconductor Thin Films Prepared by Various Deposition Methods**
K. Watanabe^{*}, H. Tokunaga, J. Yamazaki, T. Miyata and T. Minami
Optoelectronic Device System R&D Center, Kanazawa Institute of Technology

Oral Session: TCO applications

13:45-14:15

- 3pI04 Transparent Conductive Oxides and Their Applications in Near Infrared Plasmonics (INVITED)**
H. Ye^{*}, Z. Wang, C. Chen and Y. Wang
State Key Laboratory of Modern Optical Instrumentation, College of Optical Science and Engineering, Zhejiang University, Hangzhou 310027, P. R. China

14:15-14:45

- 3pI05 Transparent Conducting Materials and Their Interfaces with Soft Matter for Electronic Circuitry and Solar Electricity (INVITED)**
T.J. Marks^{1,*}
¹ Department of Chemistry, the Materials Research Center, and the Argonne-Northwestern Solar Energy Research Center Northwestern University Evanston IL 60208-3113 USA

Short Presentation 02

14:45-15:00

- 3pP11 Near and Short-Wavelength Infrared PbS Quantum Dot / ZnO Nanowire Solar Cells**
H. Wang^{1,*}, T. Kubo¹, J. Nakazaki¹ and H. Segawa^{1,2}
¹ Research Center for Advanced Science and Technology, The University of Tokyo, JAPAN ² Graduate School of Arts and Sciences, The University of Tokyo, JAPAN
- 3pP12 Electrical Properties of SnS Films Deposited by Close Spaced Sublimation Method**
Y. Iguchi¹, T. Sugiyama¹ and H. Yanagi^{1,2,*}
¹ Interdisciplinary Graduate School of Medicine and Engineering, University of Yamanashi, JAPAN ² Graduate Faculty of Interdisciplinary Research, University of Yamanashi, JAPAN
- 3pP13 Sputter-Deposition of Top Al Electrode Film for OLED Under Irradiation of Infrared Ray**
Y. Hoshi^{1,*}, Y. Yasuda¹, S. Kobayashi¹, T. Uchida¹, Y. Sawada¹, M. Wang² and H. Lei³
¹ Center for Hyper-media research, Tokyo Polytechnic University, 1853 Iiyama, Atsugi, Kanagawa 243-0297 Japan ² School of Mechanical Engineering, Shenyang University, Shenyang 110044, China ³ Surface Engineering of Materials Division, Institute of Metal Research, Chinese Academy of Sciences, Shenyang 110016, China
- 3pP14 Single Crystal Growth of Cl Doped N-Type SnS by Flux Method**
K. Inoue^{1,*}, Y. Iguchi² and H. Yanagi^{1,2,3,*}
¹ Integrated Graduate School of Medicine, Engineering, and Agricultural Sciences, University of Yamanashi, Japan ² Interdisciplinary Graduate School of Medicine and Engineering, University of Yamanashi, Japan ³ Graduate Faculty of Interdisciplinary Research, University of Yamanashi, Japan

- 3pP15** **Synthesis of Zinc Oxide Based Compound with Six Coordination Structure**
 T. Okutomi^{1,*} and H. Yanagi^{1,2,*}
¹⁾ *Integrated Graduate School of Medicine, Engineering, and Agricultural Sciences, University of Yamanashi, JAPAN* ²⁾ *Graduate Faculty of Interdisciplinary Research, University of Yamanashi, JAPAN*
- 3pP16** **Exploration of New Oxide Light-Emitting Semiconductor Thin Films Using Transition Metals**
 Y. Futakado^{1,*}, N. Watanabe¹⁾, K. Ide¹⁾, J. Kim²⁾, T. Katase¹⁾, H. Hiramatsu¹⁾, H. Hosono²⁾ and T. Kamiya¹⁾
¹⁾ *Laboratory for Materials and Structures, Tokyo Institute of Technology, Japan* ²⁾ *Materials Research Center for Element Strategy, Tokyo Institute of Technology, Japan*
- 3pP17** **A Multifunctional Plasma and Deposition Sensor for The Characterization of Plasma Sources for Film Deposition and Etching**
 M. Weise¹⁾, S. Seeger¹⁾, K. Harbauer²⁾, T. Welzel²⁾, K. Ellmer^{2*)}
¹⁾*Optotransmitter-Umweltschutz-Technologie e.V., Köpenicker Landstr. 325b, 12555 Berlin, Germany* ²⁾*Helmholtz-Zentrum Berlin für Materialien und Energie, Institute for Solar Fuels, Hahn-Meitner-Platz 1, 14109 Berlin, Germany*
- 3pP18** **Electron Scattering From Disordered Grain Boundaries in Degenerated Polycrystalline Al-Doped ZnO Thin Films**
 H. Tokunaga^{*}, T. Miyata and T. Minami
Optoelectronic Device System R&D Center, Kanazawa Institute of Technology, JAPAN
- 3pP19** **Zn-O₂ Mixture Plasma Synthesis of Near-Infrared Transparent and Opaque Films with Low Sheet Resistance**
 N. Sato and T. Ikehata
Institute of Quantum Beam Science, Ibaraki University, Hitachi 316-8511, JAPAN
- 3pP20** **Transparent Conductive Oxides with Ultra-Low Resistivity on Flexible Gas Barrier Substrates**
 T. Hara^{*}, W. Morita, T. Muto, T. Izumi and K. Nagamoto
Device Material Lab., New Materials Research Dept., Research Center, LINTEC Corporation, JAPAN
- 3pP21** **Electrical Conductivity Properties of BaO-P₂O₅ Glasses by Hydrothermal Treatment**
 M. Akamatsu^{1,2)}, H. Segawa^{1,*}, K. Watanabe³⁾, K. Iwasaki²⁾, A. Yasumori²⁾ and N. Ohashi¹⁾
¹⁾ *National Institute for Materials Science, 1-1 Namiki, Tsukuba, Ibaraki, JAPAN* ²⁾ *Department of Materials Science and Technology, Tokyo University of Science, 6-3-1 Niijyuku, Katsushika-ku, Tokyo, JAPAN* ³⁾ *Department of Molecular and Material Sciences, Kyushu University, 6-1 Kasugakoen, Kasuga, Fukuoka, JAPAN*
- 3pP22** **Application of Amorphous In₂O₃-Based Front Contact Layers in Cu(In,Ga)Se₂ Solar Cells**
 T. Koida^{*}, Y. Ueno, J. Nishinaga, H. Higuchi, H. Takahashi, M. Iioka and H. Shibata
Research Center for Photovoltaics, National Institute of Advanced Industrial Science and Technology, JAPAN
- 3pP23** **Effects of Growth Orientation on Hall Mobility in Ta:SnO₂ Epitaxial Thin Films**
 M. Fukumoto^{1,*}, S. Nakao²⁾, K. Shigematsu²⁾, D. Ogawa³⁾, K. Morikawa³⁾, Y. Hirose^{1,2)} and T. Hasegawa^{1,2)}
¹⁾ *Department of Chemistry, The University of Tokyo, 7-3-1 Hongo, Bunkyo-ku, JAPAN* ²⁾ *Kanagawa Academy of Science and Technology, 3-2-1 Sakado, Takatsu-ku, Kawasaki, JAPAN* ³⁾ *Tokyo Metropolitan Industrial Technology Research Institute (TIRI), 2-4-10 Aomi, Kouto-ku, Tokyo, JAPAN*

Short Presentation 03

15:30-15:45

- 3pP24** **Novel Indium Oxide Based Transparent Conductive Oxide Material**
 Y. Tsuchida^{1,*}, R. Akiike¹⁾, H. Hara¹⁾ and H. Kuramochi¹⁾
¹⁾ *Advanced Materials Laboratory, TOSOH Corporation, JAPAN*
- 3pP25** **Thermoelectric Properties of Amorphous IZO Thin Films and Crystalline ITO Thin Films**
 S. Kim^{1,*}, J. Byeon¹⁾ and P. Song¹⁾
Materials Science and Engineering, Pusan National University, Korea
- 3pP26** **Structural, Optical and Electrical Properties of Sputtered (ZnO)_x(InN)_{1-x} Films**

J. Jia^{*)}, T. Hara and Y. Shigesato
Graduate School of Science & Engineering, Aoyama Gakuin University

- 3pP27 Strain-Induced Modulation of Thermopower and Electrical Conductivity of LaTiO₃ Epitaxial Films on LaAlO₃ Substrate**
T. Katase^{1,2,*}, K. Ide¹, H. Hiramatsu^{1,3}, H. Hosono^{1,3} and T. Kamiya^{1,3}
¹ *Laboratory for Materials and Structures, Institute of Innovative Research, Tokyo Institute of Technology, Japan* ² *PRESTO, Japan Science and Technology Agency, Japan* ³ *Materials Research Center for Element Strategy, Tokyo Institute of Technology, Japan*
- 3pP28 Improvement of Gasochromic Properties of WO₃ Films by High Rate Reactive Sputter-Deposition on An Inclined Substrate**
Y. Yasuda^{1,*}, Y. Hoshi¹, S. Kobayashi¹, T. Uchida¹, Y. Sawada¹, M. Wang² and H. Lei³
¹ *Center for Hyper-media research, Tokyo Polytechnic University, 1853 Iiyama, Atsugi, Kanagawa 243-0297 Japan* ² *School of Mechanical Engineering, Shenyang University, Shenyang 110044, China* ³ *Surface Engineering of Materials Division, Institute of Metal Research, Chinese Academy of Sciences, Shenyang 110016, China*
- 3pP29 Characteristics of MoO₃/Ag/MoO₃ Transparent Electrode and Their Electronic Structure**
R. Kan¹, Y. Yamano¹, T. Tani², T. Uchida^{1,*}, Y. Tabira³ and I. Yashima³
¹ *Department of Media Engineering, Graduate School of Engineering, Tokyo Polytechnic University, Atsugi, Kanagawa 243-0297, JAPAN* ² *Fellow, The Society of Photography and Imaging of Japan, c/o Tokyo Polytechnic University, Nakano, Tokyo 164-8678, JAPAN* ³ *MITSUI MINING & SMELTING CO., LTD, 1333-2 Haraichi, Ageo-shi Saitama 362-0021, JAPAN*
- 3pP30 Dielectric Function of Nb-TiO₂ and TiO_{2-x} Films by Reactive Sputtering**
H. Yamamoto^{1,*}, J. Jia¹, H. Nishiyama¹ and Y. Shigesato¹
¹ *Graduate School of Science and Engineering, Aoyama Gakuin University, JAPAN*
- 3pP31 N-Type and P-Type SnOx Films Deposited by Reactive Sputtering with The Impedance Control System**
T. Sugane^{1,*}, J. Jia¹, S. Nakamura¹, D. Gloess² and Y. Shigesato¹
¹ *Graduate school of Science and Engineering, Aoyama Gakuin University, Sagamihara, Kanagawa, JAPAN,* ² *Fraunhofer-Institut für Organische Elektronik, Elektronenstrahl- und Plasmatechnik (FEP), Winterbergstrabe 28, 01277 Dresden, GERMANY*
- 3pP32 Niobium Oxide Films with Precisely Controlled Various Stoichiometry Deposited by Reactive Sputtering with The Plasma Emission Monitoring System**
M. Saito^{1,*}, J. Jia¹, S. Nakamura¹, H.M.D. Gloess³ and Y. Shigesato¹
¹ *Graduate school of Science and Engineering, Aoyama Gakuin University, Sagamihara, Kanagawa, JAPAN* ² *Core Technology Research Center, Nitto Denko Corporation, Osaka, JAPAN* ³ *Fraunhofer-Institut für Organische Elektronik, Elektronenstrahl- und Plasmatechnik (FEP), Winterbergstrabe 28, 01277 Dresden, GERMANY*
- 3pP33 Improvement of Amorphous InGaZnO Thin-Film Transistors Using High-K SrTa₂O₆ As Gate Insulator Deposited by Sputtering Method**
T. Takahashi^{1,*}, T. Hoga¹, K. Oikawa², R. Miyanaga², M.N. Fuji², Y. Uraoka² and K. Uchiyama¹
¹ *National Institute of Technology, Tsuruoka College, JAPAN* ² *Graduate School of Materials Science, Nara Institute of Science and Technology, JAPAN*
- 3pP34 Reactive sputter deposition of Gd-doped WO₃/Ag/WO₃ film for electrochromic-transparent conducting combination coatings**
Yi Yin^{1,*}, Tian Gao¹, Shouming Hu¹, and Chun Li¹
¹ *School of Optoelectronic Information, University of Electronic Science and Technology of China, CHINA*

Oral Session: Functional Oxides (TOS and TCO)

15:45-16:15

3pI06 Reactive Sputter Depositions of Various TCO Films with The Low Resistivity (INVITED)

Y. Shigesato^{1,*}, J. Jia¹, N. Oka²

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16:15-16:30

3pO01

Different Effects of Hydrogen in Amorphous In-Ga-Zn-O

K. Ide^{1,*}, H. Tang¹, Y. Kishida¹, Y. Toda², H. Hiramatsu^{1,2}, S. Matsuishi², H. Kumomi², H. Hosono^{1,2} and T. Kamiya^{1,2}

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16:30-16:45

3pO02

Growth Dynamics, Annealing Effects, and Microstructure Evolution in Amorphous In-Ga-Zn-O Observed by HAADF STEM

M. Ota^{1,*}, K. Ide¹, T.K.M. Sasase², H. Hiramatsu^{1,2}, H. Hosono^{1,2} and T. Kamiya^{1,2}

¹) *Laboratory for Materials and Structures, Tokyo Institute of Technology, JAPAN* ²) *Materials Research Center for Element Strategy, Tokyo Institute of Technology, JAPAN*

Date: July 4, 2017

Oral Session: New Materials

10:15-10:45

4aI01 Transparent P-Type CuI Films Fabricated on Plastic Sheets (INVITED)

N. Yamada^{*)}, R. Ino, H. Tomura and Y. Kondo

Department of Applied Chemistry, Chubu University

10:45-11:00

4aO01 Fabrication and characterization of (Ba,Lu)SnO₃ semiconducting epitaxial films on (111) and (001) SrTiO₃ substrates

K. Miura^{1,*)}, T. Yoshimura¹⁾, A. Ashida¹⁾, N. Fujimura¹⁾

¹⁾ Department of Physics and Electronics, Graduate School of Engineering, Osaka Prefecture University, 1-1 Gakuen-cho, Naka-ku, Sakai, Osaka, Japan

11:00-11:30

4aI02 Phosphor Identification and Synthesis Methods (INVITED)

J. Mckittrick^{1,*)}, J. Ha¹⁾, Z. Wang²⁾, G. Hirata³⁾, O. Graeve¹⁾ and S.P. Ong²⁾

¹⁾ Mechanical and Aerospace Engineering and Materials Science and Engineering, UC San Diego, 9500 Gilman Dr., La Jolla, CA USA ²⁾ Nanoengineering, and Materials Science and Engineering, UC San Diego, 9500 Gilman Dr., La Jolla, CA USA ³⁾ Center for Nanoscience and Nanotechnology, Km. 107 Carretera Tijuana-Ensenada, 22800, Ensenada, B.C. MÉXICO

11:30-11:45

4aO02 Neon-Free Operation of A KrF Excimer Laser Using Helium Buffer Gas

T. Mizunami, *.Y. Itoh and R. Sasaki

Department of Electrical Engineering and Electronics, Graduate School of Engineering, Kyushu Institute of Technology, JAPAN

Oral Session: Solar Cells

13:15-13:45

4pI03 Stable perovskite solar cells by 2D/3D interface engineering (INVITED)

G. Grancini, C. Roldán-Carmona, I. Zimmermann, M. K. Nazeeruddin^{*)}

Group for Molecular Engineering of Functional Materials, Institute of Chemical Sciences and Engineering, Ecole Polytechnique Fédérale de Lausanne, CH-1951 Sion, Switzerland.

13:45-14:15

4pI04 Hybrid Photovoltaics Using Organic Solar Cells (INVITED)

H. Segawa^{1,2,*)}

¹⁾ Department of General Systems Studies, Graduate School of Arts and Sciences, The University of Tokyo, Komaba 3-8-1, Meguro-ku, Tokyo 153-8902, JAPAN ²⁾ Research Center for Advanced Science and Technology (RCAST), The University of Tokyo, Komaba 4-6-1, Meguro-ku, Tokyo 153-8904, JAPAN

14:15-14:45

4pI05 Efficient and Stable Large-Area Perovskite Solar Cells (INVITED)

L. Han

Research Network and Facility Services Division, National Institute for Materials Science, Japan

14:45-15:00

4pO03 Deep UV Photodiodes Based on β -Ga₂O₃ / p-Type 4H-SiC Heterojunctions

S. Nakagomi^{*)}, T. Sakai, K. Kikuchi and Y. Kokubun

Faculty of Science and Engineering, Ishinomaki Senshu University, JAPAN

15:00-15:15

4pO04

Size-Dependent Optical Absorption, Ground State Energy, and Interfacial Electron Transfer Dynamics of CdSe Quantum Dots on Single Crystal Rutile-TiO₂ (001), (110), and (111) Surfaces

T. Toyoda^{1,5*}, Q. Shen^{1,5)}, K. Kamiyama²⁾, K. Katayama³⁾ and S. Hayase^{4,5)}

¹⁾ *The University of Electro-Communications, Tokyo, JAPAN* ²⁾ *Bunkoukeiki Co., Ltd., Hachoji, Tokyo, JAPAN* ³⁾ *Chuo University, Tokyo, JAPAN* ⁴⁾ *Kyushu Institute of Technology, Fukuoka, JAPAN* ⁵⁾ *JST CREST, Saitama, JAPAN*

Oral Session: Transparent Oxide Semiconductors, Photocatalysts

15:45-16:15

4pI06

Inkjet Printing Metal Oxide TFTs for OLED Display Backplane Application (INVITED)

S. Wu¹⁾, Q. Zhang¹⁾, S. Shao¹⁾, Z. Chen¹⁾ and Z. Cui^{1,*)}

¹⁾ *Printable Electronics Research Center, Suzhou Institute of Nanotech and Nanobionics, Chinese Academy of Sciences, CHINA*

16:15-16:30

4pO05

Oxygen/argon plasma treatment of amorphous ZnO-SiO₂ and application in optoelectronic devices

H. Yang^{2*)}, J. Kim^{1,3)}, H. Hosono^{1,2)}

¹⁾ *Materials Research Center for Element Strategy, Tokyo Institute of Technology, Mailbox SE-1, 4259 Nagatsuta, Midori-ku, Yokohama 226-8503, JAPAN* ²⁾ *Laboratory for Materials and Structures, Institute of Innovative Research, Tokyo Institute of Technology, 4259 Nagatsuta, Midori-ku, Yokohama 226-8503, JAPAN* ³⁾ *ACCEL Program, Japan Science and Technology Agency, Kawaguchi 332-0012, Japan*

16:30-16:45

4pO06

Room Temperature Fabricated Multi-Color Light-Emitting Thin Films Based on Ultra-Wide Bandgap Amorphous Oxide Semiconductor

N. Watanabe^{1,*)}, K. Ide¹⁾, J. Kim²⁾, H. hiramatsu^{1,2)}, T. Katase¹⁾, H. Hosono^{1,2)} and T. kamiya^{1,2)}

¹⁾ *Laboratory for Materials and Structures, Tokyo Institute of Technology* ²⁾ *Materials Research Center for Element Strategy, Tokyo Institute of Technology*

16:45-17:15

4pI07

On The Disinfection Properties of Doped TiO₂ Photocatalysts (INVITED)

G. Kiriakidis

President-elect E-MRS Univ. of Crete / IESL-FORTH, Heraklion, Crete, Greece

Date: July 5, 2017

Oral Session: Display Materials, Devices

09:30-10:00

5aI01 Defects in Amorphous Oxide Semiconductor (INVITED)

T. Kamiya^{1,2,*} and H. Hosono^{1,2)}

¹⁾ *Laboratory for Materials and Structures, Tokyo Institute of Technology, Mailbox R3-4, 4259 Nagatsuta, Midori-ku, Yokohama 226-8503, JAPAN* ²⁾ *Materials Research Center for Element Strategy, Tokyo Institute of Technology, Mailbox R3-4, 4259 Nagatsuta, Midori-ku, Yokohama 226-8503, JAPAN*

10:00-10:30

5aI02 Recent Progress of OLED Technologies including Transparent Oxides (INVITED)

T. Uchida

Department of Media Engineering, Tokyo Polytechnic University, JAPAN

10:30-11:00

5aI03 Novel Type Transparent Amorphous Oxide Semiconductors for Inverted Organic Devices (INVITED)

H. Hosono

Institute of Innovative Research and Materials Research Center for Element Strategy, Tokyo Institute of Technology

11:00-11:30

5aI04 The Dreaming OLED TV, Based on Oxide TFT Backplane (INVITED)

K. Park

LG Display

Oral Session: New fabrication methods

12:30-13:00

5pI05 Growth of Electronic Functional Oxynitride Thin Films by Pulsed Laser Deposition (INVITED)

T. Hasegawa^{1,2,3*}

¹⁾ *Department of Chemistry, The University of Tokyo, 7-3-1 Hongo, Bunkyo, Tokyo, JAPAN* ²⁾ *Kanagawa Academy of Science and Technology, 3-2-1 Sakado, Takatsu, Kawasaki, JAPAN* ³⁾ *CREST, Japan Science and Technology Agency, 7-3-1 Hongo, Bunkyo, Tokyo, JAPAN*

13:00-13:15

5pO01 Piezoelectric Properties of Novel Langasite $\text{Sr}_x\text{Ca}_{3-x}\text{TaAl}_3\text{Si}_2\text{O}_{14}$ Single Crystals

X. Fu^{1,*}, E. G. Villora¹⁾, Y. Kitanaka²⁾, Y. Noguchi²⁾, M. Miyayama²⁾, K. Shimamura^{1,3)}, N. Ohashi^{1,4)}

¹⁾ *National Institute for Materials Science, Tsukuba, JAPAN* ²⁾ *Department of Applied Chemistry, Univ. Tokyo, Bunkyo, Tokyo, JAPAN* ³⁾ *Graduate School of Advanced Science and Engineering, Waseda Univ., Shinjuku, Tokyo, JAPAN* ⁴⁾ *Materials Research Center for Element Strategy, Tokyo Inst. Tech., Midori, Yokohama, JAPAN*

13:15-13:45

5pI06 TCOs by Sputtering – Milestones of 40 Years (INVITED)

B. Szyszka¹⁾, R. Muydinov¹⁾, Stefan Körner¹⁾, M. Hartig¹⁾, D. Erfurt²⁾, R. Klenk²⁾, M.D. Heinemann²⁾, C. Kaufmann²⁾, B. Stannowski²⁾, R. Schlatmann²⁾, A. Steigert³⁾, M. Siemers⁴⁾, S. Ulrich⁴⁾, V. Sittinger⁴⁾, A. Pflug⁴⁾

¹⁾ *TU Berlin, Chair Technology of Thin Film Device TFD* ²⁾ *HZB EE-IP* ³⁾ *HZB EM-ISPEK* ⁴⁾ *Fraunhofer IST*

13:45-14:15

5pI07

Reactive Magnetron Sputtering of Ta-Doped SnO₂ Polycrystalline Films at Low Temperatures: Carrier Transport and Role of Negative Ion Bombardment (INVITED)

K. Ellmer^{1*)}, R. Mientus²⁾, J. Reck²⁾, S. Seeger²⁾, M. Weise²⁾

¹⁾ *Helmholtz-Zentrum Berlin für Materialien und Energie, Berlin, Germany* ²⁾ *Optotransmitter-Umweltschutz-Technologie e.V.*

Oral Session: Optical applications

14:45-15:15

5pI08

Review on The Development of Electrochromic Materials (INVITED)

K. Yoshimura^{*)}

National Institute of Advanced Industrial Science and Technologies (AIST), Nagoya, JAPAN

15:15-15:45

5pI09

Web Coating for Smart Glazing: Electrochromics on A Roll (INVITED)

C.G. Granqvist

Department of Engineering Sciences, The Ångström Laboratory, Uppsala University, Uppsala, Sweden

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